

<b>Notice of References Cited</b>	Application/Control No. 10/727,889	Applicant(s)/Patent Under Reexamination IYER ET AL.	
	Examiner George C. Eckert II	Art Unit 2815	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-4,992,306	02-1991	Hochberg et al.	427/255.29
	B	US-5,569,499	10-1996	Maeda et al.	427/539
	C	US-			
	D	US-			
	E	US-			
	F	US-			
	G	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Y. Nishimoto et al., Dielectric Film Deposition by Atmospheric Pressure and Low Temperature CVD using TEOS, Ozone and New Organometallic Doping Sources, June 1989, IEEE, VMIC Conference, pp. 382-89.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.